

Metals and Insulators

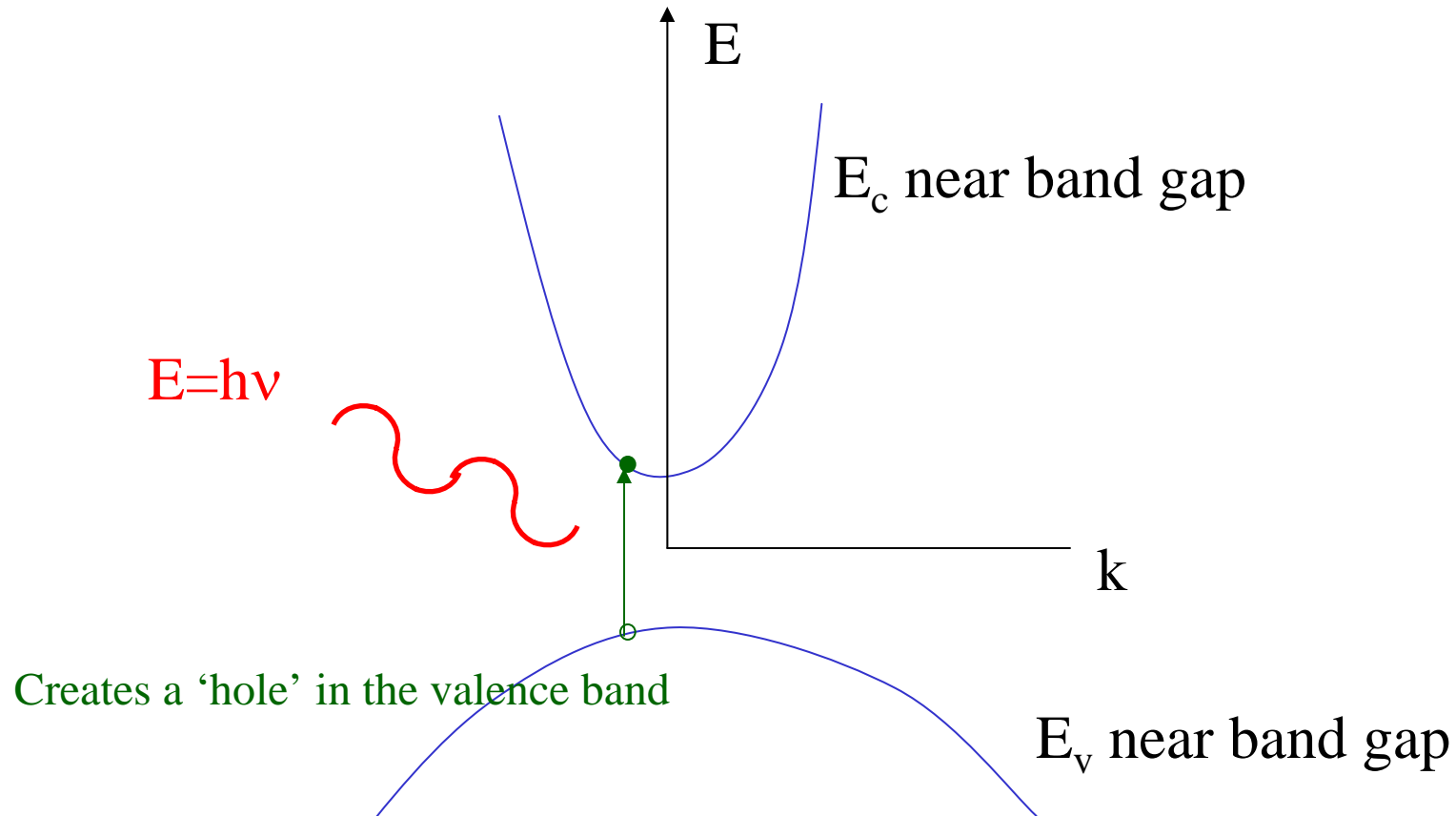
- Covalent bonds, weak U seen by e^- , with E_F being in mid-band area: free e^- , *metallic*
- Covalent or slightly ionic bonds, weak U to medium U , with E_F near band edge
 - E_F in or near kT of band edge: *semimetal*
 - E_F in gap: *semiconductor*
- More ionic bonds, large U , E_F in very large gap, *insulator*

Insulators

- Very large band gaps=no conduction electrons at reasonable temperatures
- All electrons are bound
- Optical properties of insulators are derived from the electric field being able to temporarily move electrons: **polarization**
- We will return to the interaction of E-field with bound electrons in Dielectrics Section

Semiconductors: Photon Absorption

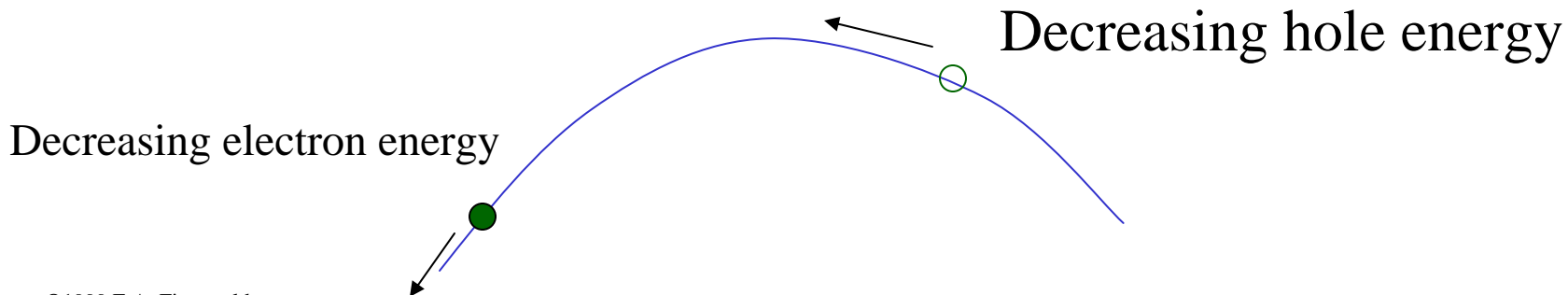
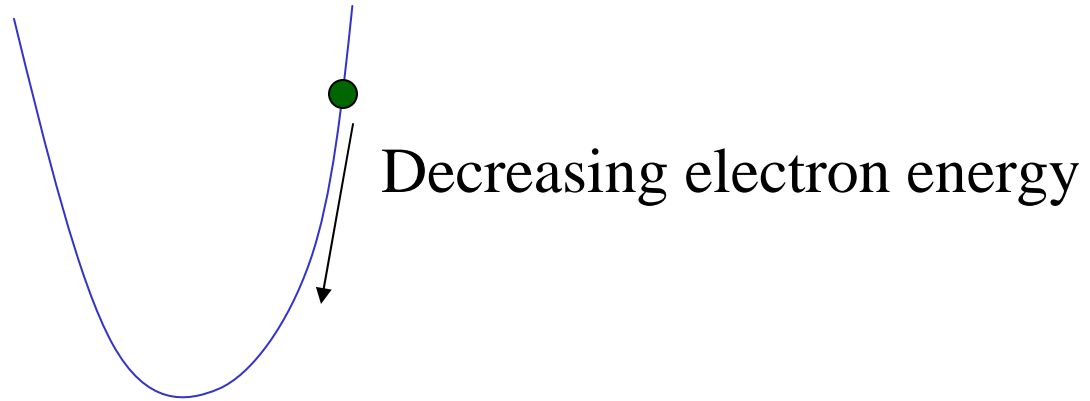
- When $E_{\text{light}} = h\nu > E_g$, an electron can be promoted from the valence band to the conduction band



Note: Most absorption near the band gap since the density of states is highest there³

Holes and Electrons

- Instead of tracking electrons in valence band, more convenient to track vacancies of electrons, or ‘holes’
- Also removes problem with negative electron mass: since hole energy increases as holes ‘sink’, the mass of the hole is positive as long as it has a positive charge
- Both carriers at the band edge can be thought of as classical free carriers like the Drude model had, as we shall see



Conductivity of Semiconductors

- Need to include both electrons and holes in the conductivity expression

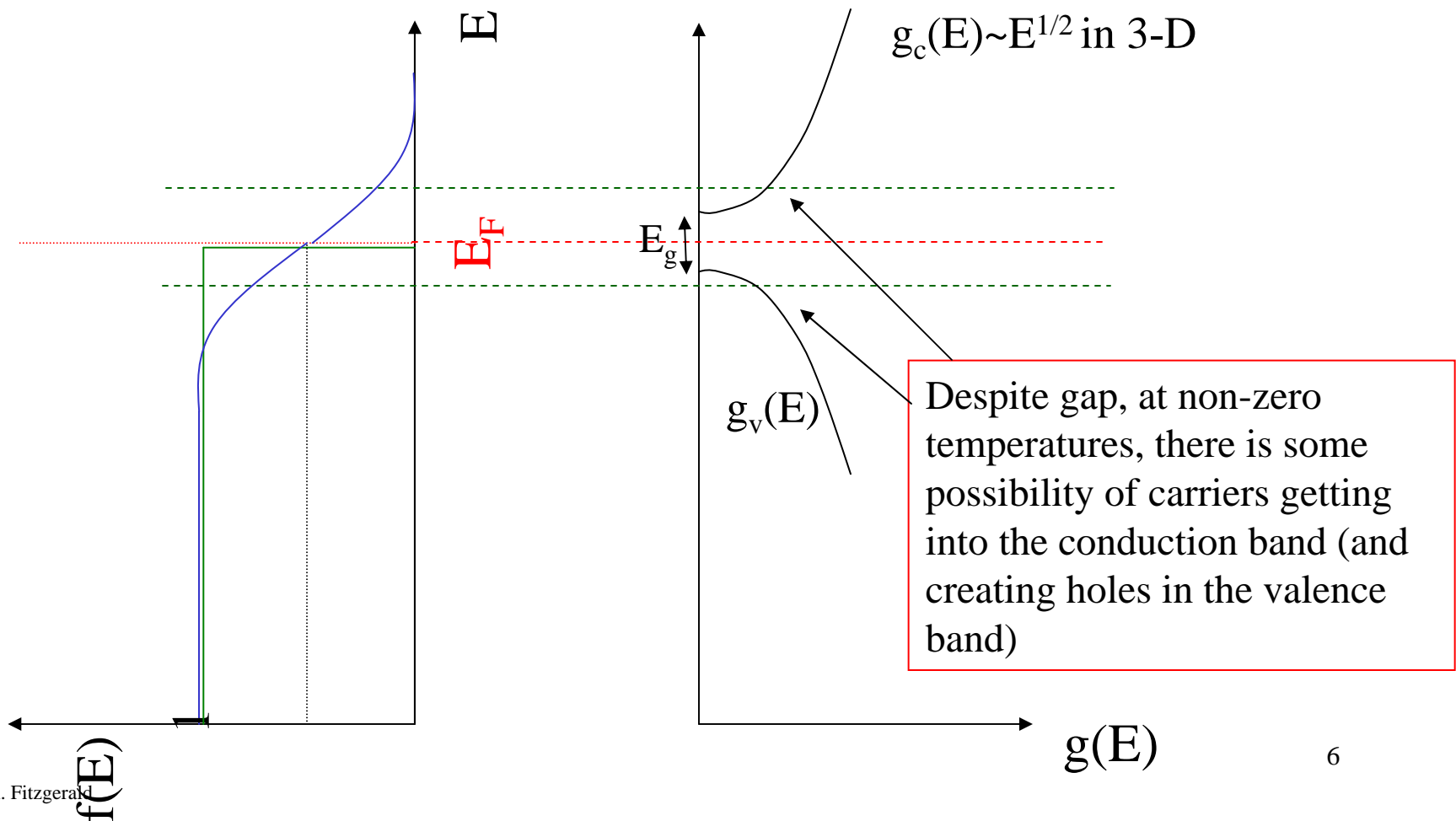
$$\sigma = ne\mu_e + pe\mu_h = \frac{ne^2\tau_e}{m_e^*} + \frac{pe^2\tau_h}{m_h^*}$$

p is analogous to n for holes, and so are τ and m^*

Note that in both photon stimulated promotion as well as thermal promotion, an equal number of holes and electrons are produced, i.e. $n=p$

Thermal Promotion of Carriers

- We have already developed how electrons are promoted in energy with T: Fermi-Dirac distribution
- Just need to fold this into picture with a band-gap



Density of Thermally Promoted of Carriers

Number of electrons per
volume in conduction
band

$$n = \int_{E_c}^{\infty} \underbrace{f(E)} \underbrace{g(E)} dE$$

Density of electron states per volume per dE

Fraction of states occupied at a particular temperature

$$f(E) = \frac{1}{e^{\frac{(E-E_F)}{k_b T}} + 1} \approx e^{-\frac{(E-E_F)}{k_b T}} \quad \text{when} \quad (E - E_F) \gg k_b T$$

$$g_c(E) = \frac{1}{2\pi^2} \left(\frac{2m_e^*}{\hbar^2} \right)^{\frac{3}{2}} (E - E_g)^{\frac{1}{2}} \longrightarrow n = \frac{1}{2\pi^2} \left(\frac{2m_e^*}{\hbar^2} \right)^{\frac{3}{2}} e^{\frac{E_F}{k_b T}} \int_{E_g}^{\infty} (E - E_g)^{\frac{1}{2}} e^{\frac{-E}{k_b T}} dE$$

$$\text{Since } \int_0^{\infty} x^{\frac{1}{2}} e^{-x} dx = \frac{\sqrt{\pi}}{2}, \text{ then } n = 2 \underbrace{\left(\frac{m_e^* k_b T}{2\pi \hbar^2} \right)^{\frac{3}{2}}}_{N_C} e^{\frac{E_F}{k_b T}} e^{\frac{-E_g}{k_b T}}$$

$$n = N_C e^{\frac{E_F - E_g}{k_b T}}$$

Density of Thermally Promoted of Carriers

- A similar derivation can be done for holes, except the density of states for holes is used
- Even though we know that $n=p$, we will derive a separate expression anyway since it will be useful in deriving other expressions

$$g_v(E) = \frac{1}{2\pi^2} \left(\frac{2m_h^*}{\hbar^2} \right)^{\frac{3}{2}} (-E)^{\frac{1}{2}} \longrightarrow p = \int_{-\infty}^0 f_h(E) g_v(E) dE, \text{ where } f_h = 1 - f(E)$$

$$p = 2 \left(\frac{m_h^* k_b T}{2\pi\hbar^2} \right)^{\frac{3}{2}} e^{\frac{-E_F}{k_b T}}$$

$$p = N_v e^{\frac{-E_F}{k_b T}}$$

Thermal Promotion

- Because electron-hole pairs are generated, the Fermi level is approximately in the middle of the band gap
- The law of mass action describes the electron and hole populations, since the total number of electron states is fixed in the system

$$n = p \text{ gives } E_F = \frac{E_g}{2} + \frac{3}{4} k_b T \ln \left(\frac{m_h^*}{m_e^*} \right)$$

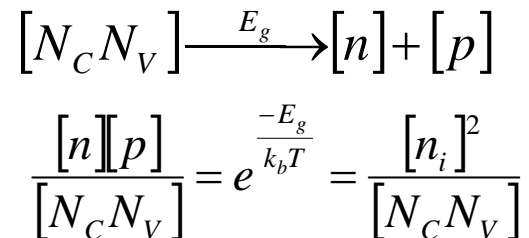
Since m_e^* and m_h^* are close and in the \ln term, the Fermi level sits about in the center of the band gap

$$p \text{ or } n = n_i = 2 \left(\frac{k_b T}{2\pi\hbar^2} \right)^{\frac{3}{2}} (m_e^* m_v^*)^{\frac{3}{4}} e^{\frac{-E_g}{2k_b T}}$$

Law of Mass Action for Carrier Promotion

$$n_i^2 = np = 4 \left(\frac{k_b T}{2\pi\hbar^2} \right)^3 (m_e^* m_h^*)^{\frac{3}{2}} e^{\frac{-E_g}{k_b T}} \quad ; \quad n_i^2 = N_C N_V e^{\frac{-E_g}{k_b T}}$$

- Note that re-arranging the right equation leads to an expression similar to a chemical reaction, where E_g is the barrier
- $N_C N_V$ is the density of the reactants, and n and p are the products



- Thus, a method of changing the electron or hole population without increasing the population of the other carrier will lead to a dominant carrier type in the material
- Photon absorption and thermal excitation produce only pairs of carriers: *intrinsic semiconductor*
- Increasing one carrier concentration without the other can only be achieved with impurities, also called doping: *extrinsic semiconductors*

Intrinsic Semiconductors

- Conductivity at any temperature is determined mostly by the size of the band gap
- All intrinsic semiconductors are insulating at very low temperatures

Recall:
$$\sigma = ne\mu_e + pe\mu_h = \frac{ne^2\tau_e}{m_e^*} + \frac{pe^2\tau_h}{m_h^*}$$

$$\sigma_{\text{int}} = n_i e (\mu_e + \mu_h) \propto e^{\frac{-E_g}{2k_b T}}$$

This can be a measurement for E_g

For Si, $E_g=1.1\text{eV}$, and let μ_e and μ_h be approximately equal at $1000\text{cm}^2/\text{V-sec}$ (very good Si!)

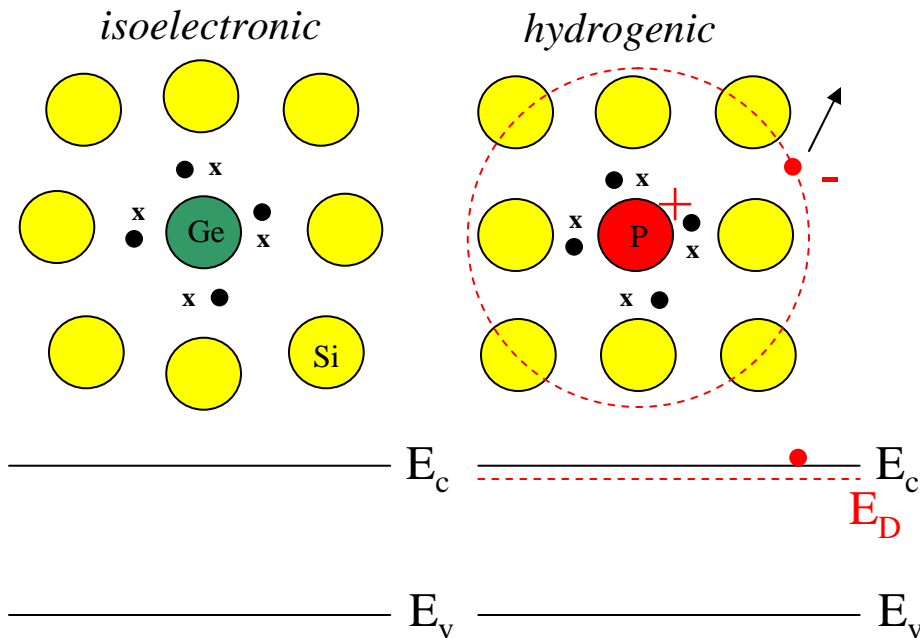
$\sigma \sim 10^{10}\text{cm}^{-3} * 1.602 \times 10^{-19} * 1000\text{cm}^2/\text{V-sec} = 1.6 \times 10^{-6} \text{ S/m}$, or a resistivity ρ of about 10^6 ohm-m max

- One important note: No matter how pure Si is, the material will always be a poor insulator at room T
- As more analog wireless applications are brought on Si, this is a major issue for system-on-chip applications
 - E-M waves lose strength since e- are responding to wave: loss and low Q resonant circuits

Extrinsic Semiconductors

- Adding 'correct' impurities can lead to controlled domination of one carrier type
 - n-type is dominated by electrons
 - p-type if dominated by holes
- Adding other impurities can degrade electrical properties

Impurities with close electronic structure to host



Impurities with very different electronic structure to host

